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**Patent and Trademark Office**

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### LIST OF DOCUMENTS CITED BY APPLICANT

(Use several sheets if necessary)

**Applicants:**

Satoshi Watanabe

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## U. S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
YCT		5,569,784	10/29/96	Watanabe et al.	564	430	
YCT		5,580,695	12/03/96	Murata et al.	430	270.1	
YCT		5,972,559	10/26/99	Watanabe et al.	430	270.1	
YCT		6,150,068	11/21/00	Sato et al.	430	270.1	

## FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation Yes   No
YCT		5249683	09/28/93	Japan	G03F	007/075	X (abstract)
YCT		10048814 A	02/20/98	Japan	G03F	007/004	X (abstract)
YCT		10073912	03/17/98	Japan	G03F	001/00	X (abstract)
YCT		10133371	05/22/98	Japan	G03F	007/029	X (abstract)
YCT		10142777	05/29/98	Japan	G03F	007/004	X (abstract)
YCT		10319581 A	12/04/98	Japan	G03F	007/004	X (abstract)

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

yct	Hinsberg et al., "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," <i>Journal of Photopolymer Science and Technology</i> , 6(4): 535-546 (1993).
yct	Houlihan et al., "A Study of Resist Outgassing as a Function of Differing Phot additives," <i>Proc. SPIE</i> , 3678: 264-274 (1999).
yct	Uetani et al., "Positive ArF Resist with 2EAdMA/GBLMA Resin System," <i>Proc. SPIE</i> , 3678: 510-517 (1999).

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Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.